

L Number	Hits	Search Text	DB	Time stamp
-	363	("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)	USPAT; EPO; JPO; DERWENT; IBM_TDB	2003/12/19 02:14
-	102	((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and plasma and etch\$3	USPAT; EPO; JPO; DERWENT; IBM_TDB	2001/03/05 14:56
-	55	((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))	USPAT; EPO; JPO; DERWENT; IBM_TDB	2001/03/05 15:19
-	16	((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))) and plasma and etch\$3	USPAT; EPO; JPO; DERWENT; IBM_TDB	2001/03/05 15:20
-	0	((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))) and etch\$3 not (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))) and plasma and etch\$3)	USPAT; EPO; JPO; DERWENT; IBM_TDB	2001/03/05 15:17
-	4	((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))) and plasma not (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))) and plasma and etch\$3)	USPAT; EPO; JPO; DERWENT; IBM_TDB	2001/03/06 13:29
-	124	((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (argon ar) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride))	USPAT; EPO; JPO; DERWENT; IBM_TDB	2001/03/05 15:21

-	20	<p>((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (argon ar) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride))) and plasma and etch\$3 not (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))) and plasma and etch\$3) (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))) and plasma not (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))) and plasma and etch\$3)))</p>	USPAT; EPO; JPO; DERWENT; IBM_TDB	2001/03/05 15:53
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	2	<p>((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (argon ar) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride))) and etch\$3 not (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar))) and plasma and etch\$3) (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar))) and plasma not (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar))) and plasma and etch\$3) (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar))) and plasma and etch\$3) not (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar))) and plasma and etch\$3) (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar))) and plasma not (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and ("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar))) and plasma and etch\$3))))))</p>	USPAT; EPO; JPO; DERWENT; IBM_TDB	2001/03/05 15:53
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-	16	<p>((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (argon ar) and (("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride))) and plasma not (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar))) and plasma and etch\$3) (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar))) and plasma and etch\$3) (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (argon ar) and (("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride))) and plasma and etch\$3 not (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar))) and plasma and etch\$3) (((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar))) and plasma and etch\$3))))))</p>	<p>USPAT; EPO; JPO; DERWENT; IBM_TDB</p>	2001/03/05 15:54
-	24	<p>US-Re30505-\$.DID. OR US-4615764-\$.DID. OR US-4793897-\$.DID. OR US-5211790-\$.DID. OR US-5362361-\$.DID. OR US-5397431-\$.DID. OR US-5721090-\$.DID. OR US-5753418-\$.DID. OR US-5779926-\$.DID. OR US-5817579-\$.DID. OR US-5910392-\$.DID. OR US-5911887-\$.DID.</p>	<p>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</p>	2003/12/18 15:49

-	15	US-Re30505-\$.DID. OR US-4615764-\$.DID. OR US-4793897-\$.DID. OR US-5211790-\$.DID. OR US-5362361-\$.DID. OR US-5397431-\$.DID. OR US-5721090-\$.DID. OR US-5753418-\$.DID. OR US-5779926-\$.DID. OR US-5817579-\$.DID. OR US-5910392-\$.DID. OR US-5911887-\$.DID. OR US-6080678-\$.DID. OR US-6110826-\$.DID. OR US-6132631-\$.DID.	USPAT	2003/12/18 15:49
-	30	US-Re30505-\$.DID. OR US-4615764-\$.DID. OR US-4793897-\$.DID. OR US-5211790-\$.DID. OR US-5362361-\$.DID. OR US-5397431-\$.DID. OR US-5721090-\$.DID. OR US-5753418-\$.DID. OR US-5779926-\$.DID. OR US-5817579-\$.DID. OR US-5910392-\$.DID. OR US-5911887-\$.DID. OR US-6080678-\$.DID. OR US-6110826-\$.DID. OR US-6132631-\$.DID.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/18 15:51
-	0	WO9616437	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/18 15:51
-	3	"9616437"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/18 15:52
-	33	(US-Re30505-\$.DID. OR US-4615764-\$.DID. OR US-4793897-\$.DID. OR US-5211790-\$.DID. OR US-5362361-\$.DID. OR US-5397431-\$.DID. OR US-5721090-\$.DID. OR US-5753418-\$.DID. OR US-5779926-\$.DID. OR US-5817579-\$.DID. OR US-5910392-\$.DID. OR US-5911887-\$.DID. OR US-6080678-\$.DID. OR US-6110826-\$.DID. OR US-6132631-\$.DID.) "9616437"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/18 15:59
-	15	etch\$3 and DUV and (nitride Si3N4 "Si.sub.3 N.sub.4") and (("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same (fluoride fluorine "CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/18 16:37
-	0	20020003126.URPN.	USPAT	2003/12/18 16:13
-	0	20020003126.URPN.	USPAT	2003/12/18 16:13
-	1	2002-178961.NRAN.	DERWENT	2003/12/18 16:13
-	33	((US-Re30505-\$.DID. OR US-4615764-\$.DID. OR US-4793897-\$.DID. OR US-5211790-\$.DID. OR US-5362361-\$.DID. OR US-5397431-\$.DID. OR US-5721090-\$.DID. OR US-5753418-\$.DID. OR US-5779926-\$.DID. OR US-5817579-\$.DID. OR US-5910392-\$.DID. OR US-5911887-\$.DID. OR US-6080678-\$.DID. OR US-6110826-\$.DID. OR US-6132631-\$.DID.) "9616437") not (etch\$3 and DUV and (nitride Si3N4 "Si.sub.3 N.sub.4") and (("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same (fluoride fluorine "CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/18 16:17
-	99	etch\$3 and (photoresist resist DUV) and (nitride Si3N4 "Si.sub.3 N.sub.4") and (("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same (fluoride fluorine "CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/18 16:38
-	119	etch\$3 and (organic photoresist resist DUV) and (nitride Si3N4 "Si.sub.3 N.sub.4") and (("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same (fluoride fluorine "CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/18 16:39
-	21	(etch\$3 and (organic photoresist resist DUV) and (nitride Si3N4 "Si.sub.3 N.sub.4") and (("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same (fluoride fluorine "CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6))) and selecti\$5 same (organic photoresist resist DUV) same (nitride Si3N4 "Si.sub.3 N.sub.4")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/18 16:40

-	4	((("RE30505") or ("5211790") or ("5753418") or ("5817579"))).PN.	USPAT	2003/12/19 01:27
-	0	20020003126.URPN.	USPAT	2003/12/19 02:05
-	1	2002-178961.NRAN.	DERWENT	2003/12/19 02:05
-	6	etch\$3 and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$2oxide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj \$4fluoride) and (HBr hydrogen adj bromide)	USPAT; EPO; JPO; DERWENT; IBM_TDB	2003/12/19 02:22
-	5	etch\$3 same (nitride SiN Si3N4 "Si.sub.3 N.sub.4" DUV resist photoresist) and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$2oxide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj \$4fluoride) and (HBr hydrogen adj bromide)	USPAT; EPO; JPO; DERWENT; IBM_TDB	2003/12/19 02:21
-	2	etch\$3 same (nitride SiN Si3N4 "Si.sub.3 N.sub.4" DUV resist photoresist) and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$2oxide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj \$4fluoride) same (HBr hydrogen adj bromide)	USPAT; EPO; JPO; DERWENT; IBM_TDB	2003/12/19 02:21
-	29	etch\$3 same (nitride SiN Si3N4 "Si.sub.3 N.sub.4" DUV resist photoresist) and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$2oxide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj \$4fluoride)	USPAT; EPO; JPO; DERWENT; IBM_TDB	2003/12/19 02:22
-	60	etch\$3 and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$2oxide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj \$4fluoride)	USPAT; EPO; JPO; DERWENT; IBM_TDB	2003/12/19 02:22
-	24	(US-6132631-\$ or US-5911887-\$ or US-6080678-\$ or US-6110826-\$ or US-5910392-\$ or US-5362361-\$ or US-5721090-\$ or US-5397431-\$ or US-5779926-\$ or US-4615764-\$ or US-4793897-\$ or US-5877075-\$ or US-6015597-\$ or US-6617257-\$ or US-6261905-\$ or US-6204168-\$ or US-5824604-\$ or US-5798562-\$ or US-5445712-\$ or US-4431477-\$ or US-6225220-\$ or US-6149828-\$).did. or (US-20010005623-\$ or US-20020076935-\$).did.	USPAT; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB	2003/12/19 02:33
-	18	etch\$3 same (nitride SiN Si3N4 "Si.sub.3 N.sub.4" DUV resist photoresist) and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$2oxide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj \$4fluoride)) not ((etch\$3 and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$2oxide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj \$4fluoride) and (HBr hydrogen adj bromide)) ((US-6132631-\$ or US-5911887-\$ or US-6080678-\$ or US-6110826-\$ or US-5910392-\$ or US-5362361-\$ or US-5721090-\$ or US-5397431-\$ or US-5779926-\$ or US-4615764-\$ or US-4793897-\$ or US-5877075-\$ or US-6015597-\$ or US-6617257-\$ or US-6261905-\$ or US-6204168-\$ or US-5824604-\$ or US-5798562-\$ or US-5445712-\$ or US-4431477-\$ or US-6225220-\$ or US-6149828-\$).did. or (US-20010005623-\$ or US-20020076935-\$).did.))	USPAT	2003/12/19 02:53

-	26	(etch\$3 and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$2oxide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj \$4fluoride)) not ((etch\$3 same (nitride SiN Si3N4 "Si.sub.3 N.sub.4" DUV resist photoresist) and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$2oxide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj \$4fluoride)) (etch\$3 and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$2oxide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj \$4fluoride) and (HBr hydrogen adj bromide)) ((US-6132631-\$ or US-5911887-\$ or US-6080678-\$ or US-6110826-\$ or US-5910392-\$ or US-5362361-\$ or US-5721090-\$ or US-5397431-\$ or US-5779926-\$ or US-4615764-\$ or US-4793897-\$ or US-5877075-\$ or US-6015597-\$ or US-6617257-\$ or US-6261905-\$ or US-6204168-\$ or US-5824604-\$ or US-5798562-\$ or US-5445712-\$ or US-4431477-\$ or US-6225220-\$ or US-6149828-\$).did. or (US-20010005623-\$ or US-20020076935-\$).did.))	USPAT	2003/12/19 02:53
-	26	(US-5877075-\$ or US-6149828-\$ or US-6015597-\$ or US-6110826-\$ or US-6132631-\$ or US-6080678-\$ or US-5911887-\$ or US-5910392-\$ or US-5779926-\$ or US-5721090-\$ or US-5397431-\$ or US-5362361-\$ or US-4793897-\$ or US-4615764-\$ or US-6444559-\$ or US-6617257-\$ or US-6261905-\$ or US-6204168-\$ or US-5824604-\$ or US-5798562-\$ or US-5445712-\$ or US-4431477-\$ or US-6225220-\$ or US-5114827-\$).did. or (US-20010005623-\$ or US-20020076935-\$).did.	USPAT; US-PGPUB	2003/12/29 11:59
-	5	((US-5877075-\$ or US-6149828-\$ or US-6015597-\$ or US-6110826-\$ or US-6132631-\$ or US-6080678-\$ or US-5911887-\$ or US-5910392-\$ or US-5779926-\$ or US-5721090-\$ or US-5397431-\$ or US-5362361-\$ or US-4793897-\$ or US-4615764-\$ or US-6444559-\$ or US-6617257-\$ or US-6261905-\$ or US-6204168-\$ or US-5824604-\$ or US-5798562-\$ or US-5445712-\$ or US-4431477-\$ or US-6225220-\$ or US-5114827-\$).did. or (US-20010005623-\$ or US-20020076935-\$).did.) and (DUV deep adj (UV ultra\$6))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/29 12:09
-	3	((US-5877075-\$ or US-6149828-\$ or US-6015597-\$ or US-6110826-\$ or US-6132631-\$ or US-6080678-\$ or US-5911887-\$ or US-5910392-\$ or US-5779926-\$ or US-5721090-\$ or US-5397431-\$ or US-5362361-\$ or US-4793897-\$ or US-4615764-\$ or US-6444559-\$ or US-6617257-\$ or US-6261905-\$ or US-6204168-\$ or US-5824604-\$ or US-5798562-\$ or US-5445712-\$ or US-4431477-\$ or US-6225220-\$ or US-5114827-\$).did. or (US-20010005623-\$ or US-20020076935-\$).did.) and (DUV deep adj (UV ultra\$6))) and (nitride sin si3n4 "si.sub.3 N.sub.4")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/29 12:08

-	3	((((US-5877075-\$ or US-6149828-\$ or US-6015597-\$ or US-6110826-\$ or US-6132631-\$ or US-6080678-\$ or US-5911887-\$ or US-5910392-\$ or US-5779926-\$ or US-5721090-\$ or US-5397431-\$ or US-5362361-\$ or US-4793897-\$ or US-4615764-\$ or US-6444559-\$ or US-6617257-\$ or US-6261905-\$ or US-6204168-\$ or US-5824604-\$ or US-5798562-\$ or US-5445712-\$ or US-4431477-\$ or US-6225220-\$ or US-5114827-\$).did. or (US-20010005623-\$ or US-20020076935-\$).did.) and (DUV deep adj (UV ultra\$6))) and (nitride sin si3n4 "si.sub.3 N.sub.4")) and etch\$3 same (nitride sin si3n4 "si.sub.3 N.sub.4")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/29 12:02
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